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Jc837 U.S. PTO

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Address to:
Box Patent Application
Assistant Commissioner for Patents
Washington, D.C. 20231

Attorney's Docket No. LMPY-6410
[217/U]
First Named Inventor Juergen Kleinschmidt

UTILITY PATENT APPLICATION TRANSMITTAL
(under 37 CFR 1.53(b))

Jc542 U.S. PTO
09/602184
06/22/00

SIR:

Transmitted herewith for filing is the patent application entitled:
NARROW BAND EXCIMER LASER WITH A PRISM-GRATING AS LINE-NARROWING OPTICAL
ELEMENT

CERTIFICATION UNDER 37 CFR § 1.10

I hereby certify that this New Application and the documents referred to as enclosed herein are being
deposited with the United States Postal Service on this date June 22, 2000, in an envelope bearing
"Express Mail Post Office To Addressee" Mailing Label Number EL387336193US addressed to: Box
Patent Application, Assistant Commissioner for Patents, Washington, D.C. 20231.

LANA T. BRENNER

[Signature]

(Name of person mailing paper)

(Signature)

Enclosed are:

1. ☒ Transmittal Form (two copies required)
2. The papers required for filing date under CFR § 1.53(b):
 - i. 30 Pages of specification (including claims and abstract);
 - ii. 5 Sheets of drawings.

☐ formal ☒ informal
3. Declaration or oath
 - a. ☒ Unexecuted (original or copy)
4. ☐ Microfiche Computer Program (Appendix, see 37 CFR 1.96)
5. ☐ Nucleotide and/or Amino Acid Sequence Submission (if applicable, all necessary)
 - i. ☐ Computer Readable Copy
 - ii. ☐ Paper Copy (identical to computer copy)
 - iii. ☐ Statement verifying identity of above copies

ACCOMPANYING APPLICATION PARTS

6. ☐ An assignment of the invention to is attached (including Form PTO-1595).
 - i. ☐ 37 CFR 3.73(b) Statement (when there is an assignee)
7. ☐ Power of Attorney
8. ☐ An Information Disclosure Statement (IDS) is enclosed, including a PTO-1449 and copies of ☐ references.
9. ☐ Preliminary Amendment.
10. ☒ Return Receipt Postcard (MPEP 503 -- should be specifically itemized)
11. ☐ Other

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12. FOREIGN PRIORITY

☐ Priority of application no. ___ filed on ___ in ___ is claimed under 35 USC 119.

The certified copy of the priority application:

- ☐ is filed herewith; or
- ☐ has been filed in prior application no. ___ filed on ___, or
- ☐ will be provided.
- ☐ English Translation Document (if applicable)

13. FEE CALCULATION

a. ☐ Amendment changing number of claims or deleting multiple dependencies is enclosed.

CLAIMS AS FILED

	Number Filed	Number Extra	Rate	Basic Fee (\$690)
Total Claims	103 - 20	* 83	x \$18.00	\$1494
Independent Claims	8 - 3	* 5	x \$78.00	\$390
<input checked="" type="checkbox"/> Multiple dependent claim(s), if any			\$260.00	\$260.00

*If less than zero, enter "0".

Filing Fee Calculation \$2834.00

50% Filing Fee Reduction (if applicable) \$

14. Small Entity Status

- a. ☐ A small entity statement is enclosed.
- b. ☐ A small entity statement was filed in the prior nonprovisional application and such status is still proper and desired.
- c. ☐ is no longer claimed.

15. Other Fees

- ☐ Recording Assignment [\$40.00] \$
- ☐ Other fees \$
- Specify _____ \$
- Total Fees Enclosed \$2834.00

16. Payment of Fees

- ☒ Check(s) in the amount of \$ 2834.00 enclosed.
- ☐ Charge Account No. 12-1420 in the amount of \$__.
- A duplicate of this transmittal is attached.**

17. All correspondence regarding this application should be forwarded to the undersigned attorney:

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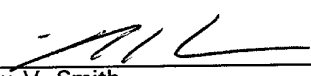
18. Authorization to Charge Additional Fees

- ☒ The Commissioner is hereby authorized to charge any additional fees (or credit any overpayment) associated with this communication and which may be required under 37 CFR § 1.16 or § 1.17 to Account No. 12-1420. **A duplicate of this transmittal is attached.**

LIMBACH & LIMBACH L.L.P.

June 22, 2000
(Date)

Attorney Docket No. LMPY-6410
[217/U]

By: 
Andrew V. Smith
Registration No. 43,132
Attorney(s) or Agent(s) of Record

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE
APPLICATION FOR PATENT

INVENTOR: Juergen Kleinschmidt and Thomas Schroder

TITLE: Narrow Band Excimer Laser with a Prism-Grating as
Line-Narrowing Optical Element

ATTY DOCKET: LMPY-6410 (217/U)

Priority

This application claims the benefit of priority to United States provisional patent application no. 60/140,532, filed June 23, 1999, 60/173,993, filed December 30, 1999, 60/170,919, filed December 15, 1999 and 60/167,835, filed November 29, 1999, each of which is hereby incorporated by reference.

Background of the Invention

1. Field of the Invention

The invention relates to line-narrowed excimer and molecular fluorine excimer and molecular fluorine laser systems, and particularly to a grating arrangement having a dielectric coating with comparatively high damage thresholds to radiation induced degradation which can be used as a line narrowing element in line narrowed excimer lasers, and also particularly to a line-narrowed laser resonator including a grating-prism element, or grism, preferably having a dielectric, antireflection (AR) coating on any transmitting surfaces and a dielectric, highly reflective (HR) coating on any reflection surfaces.

2. Discussion of the Related Art

Semiconductor manufacturers are currently using deep ultraviolet (DUV) lithography tools based on KrF-excimer laser systems operating

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around 248 nm, as well as the following generation of ArF-excimer laser systems operating around 193 nm. The ArF and KrF lasers have a broad characteristic bandwidth around 600 pm (FWHM). Vacuum UV (VUV) will use the F2-laser which characteristically emits two or three closely spaced lines around 157 nm.

It is important for their respective applications to the field of sub-quarter micron silicon processing that each of the above laser systems become capable of emitting a narrow spectral band of known bandwidth and around a very precisely determined and finely adjustable absolute wavelength. Techniques for reducing bandwidths by special resonator designs to less than 100 pm (for ArF and KrF lasers) for use with all-reflective optical imaging systems, and for catadioptric imaging systems to less than 0.6 pm, are being continuously improved upon.

For the application of excimer lasers as light sources for steppers and/or scanners for photographic microlithography, it is desired to have laser emission within a range that is much small than the natural linewidth which is approximately 300 to 400 pm for ArF and KrF lasers. The extent of the desired line narrowing depends on the imaging optics of the stepper/scanner devices. The desired bandwidth for catadioptric systems is less than around 50 pm, and for refractive optics it is less than around 0.8 pm. Currently, used systems for the KrF laser emitting around 248 nm have a bandwidth around 0.6 pm. To improve the resolution of the projection optics, a narrower laser bandwidth is desired for excimer laser systems of high reliability and very small bandwidth of 0.4 pm or less.

A line-narrowed excimer or molecular fluorine laser used for microlithography provides an output beam with specified narrow spectral linewidth. It is desired that parameters of this output beam such as wavelength, linewidth, and energy and energy dose stability be reliable and consistent. Narrowing of the linewidth is generally achieved through the use of a linewidth narrowing and/or wavelength selection and wavelength tuning module (hereinafter "line-narrowing module")

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The line-narrowing module typically functions to disperse incoming light angularly such that light rays of the beam with different wavelengths are reflected at different angles. Only those rays fitting into a certain "acceptance" angle of the resonator undergo further amplification, and eventually contribute to the output of the laser system.

Excimer lasers typically use planar gratings for narrow linewidth oscillation. The bandwidth $\Delta\lambda$ of the radiation is nearly given by, for a Gaussian line shape:

$\lambda \equiv$ emission wavelength;
 $\Delta\Theta \equiv$ divergence of the beam in front of the grating;
 $\alpha \equiv$ blaze angle of the grating;
 $m \equiv$ effective number of round trips of the beam in the laser resonator.

Typical grating substrates are made by Zerodure or ULE. A layer of epoxy is typically formed directly on the surface of the grating substrate, wherein the epoxy layer has a thickness between 12-40 μm . The epoxy surface is then typically coated by aluminum, wherein the thickness of the aluminum coating is between 10-30 μm .

A disadvantage of these types of gratings is that the aluminum absorbs more than 10% of the incident radiation power in the DUV spectral region within a very thin layer thickness. As a result, the gratings vary in their response to the exposure to high power laser beams

Summary of the Invention

It is another object to provide a dispersive line-narrowing element for producing substantial line-narrowing in an excimer or molecular fluorine laser system that experiences relatively low absorption of incident laser radiation, such response variance due to heating and aging and effects of nonuniform heating are also relatively low.

Further in accordance with the above objects, a grating element is provided for use with a line-narrowing package of an excimer or molecular fluorine laser including a dielectric AR coating. This grating having the dielectric AR coating is configured to be disposed in a laser resonator in front of a resonator reflector, such as a HR mirror or partially reflective outcoupling mirror.

In a first aspect, the grism may be configured to be disposed in the laser resonator with the grating surface facing the discharge chamber and serving as a HR reflecting resonator reflector. The grism according to the first aspect has a dielectric HR coating on its grating surface.

In a third aspect, the grism may be configured to be disposed in the laser resonator with the grating surface facing the discharge chamber and the rear surface of the prism portion serving as a HR reflecting resonator reflector. The grism according to the third aspect has a dielectric AR coating on the grating surface and a dielectric HR coating on the back surface of the prism portion. The grism may be disposed at a selected orientation with respect to the longitudinal cross section of the resonator, such that the prism portion of the grism may serve as a beam expanding prism.

In a fourth aspect, the grism may be configured to be disposed in the laser resonator with preferably the grating surface and alternatively the prism portion facing the discharge chamber, wherein neither the grating surface nor the entry/exit surface of the prism portion serves as a HR reflecting resonator reflector. The grism according to the fourth aspect has a dielectric AR coating on each of the grating surface and the entry/exit surface of the prism portion. In use, the grism is preferably disposed in front of a HR resonator reflecting mirror or partially reflecting outcoupling mirror. The grism may be disposed with the prism portion

facing the discharge chamber and at a selected orientation with respect to the longitudinal cross section of the resonator, such that the prism portion of the grism may serve as a beam expanding prism.

In a fifth aspect, the grism may be configured to be disposed in the laser resonator as an output coupling element with either the grating surface or prism portion facing the discharge chamber, and, in either case, either the grating surface or prism portion serving as a partially reflecting resonator reflector surface. In this case, the surface that serves as the partially reflecting resonator reflector surface is partially reflecting and may be uncoated or coated, while the other surface has a dielectric AR coating on it.

Brief Description of the Drawings

Fig. 1 schematically illustrates an excimer or molecular fluorine laser system in accord with a preferred embodiment.

Fig. 2 schematically illustrates a ray path through a transmission grism.

Fig. 3a schematically illustrates a first embodiment of a laser resonator including a grism for line-narrowing and/or line-selection having a reflective grating surface facing the discharge chamber.

Fig. 3b schematically shows a preferred grism for use with the first embodiment of Fig. 3a having a dielectric HR coating on the grating surface.

Fig. 3c schematically shows a preferred grating which may be used with a line-narrowing and/or line-selection package of the preferred embodiment of Fig. 1 or instead of the grism of the first embodiment of Fig. 3a.

Fig. 4a schematically shows a second embodiment of a laser resonator including a grism for line-narrowing and/or line-selection having a transmissive prism portion including a beam entry/exit surface facing the discharge chamber.

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Fig. 7b schematically shows a preferred grism for use with the fifth embodiment having a dielectric AR coating on the beam entry/exit surface of the prism portion and a dielectric HR coating on a grating surface.

What follows is a cite list of references each of which is, in addition to those references cited above in the priority section, hereby incorporated by reference into the detailed description of the preferred embodiment below, as disclosing alternative embodiments of elements, or disclosing features of the preferred embodiments not otherwise set forth in detail below. A single one or a combination of two or more of these references may be consulted to obtain a variation of the preferred

U.S. patent applications no. 09/317,695, 09/130,277, 09/244,554, 09/317,527, 09/484,818, 60/140,531, 60/141,678, 60/147,219, 60/170,342, 60/178,445, 60/173,993, 60/166,277, 60/166,967, 60/167,835, 60/170,919, and 60/202,564, and U.S. patent no. 5,761,236, each of which is assigned to the same assignee as the present application, and U.S. patents no. 5,652,681, 5,625,499, 5,999,318 and 4,803,696; and

N.A. Finkelstein et al., A rectilinear transmission grating, JOSA 43, 335 (1953);

R. Hultzsich, Gitterprismen; Photonik, p. 40-41 (Sept. 98);

W. Demtroeder, *Lawser Spectroscopy*, Springer, Berlin Heidelberg, p. 112 (1996).

Referring to Fig. 1, a DUV or VUV laser system, preferably an excimer, such as ArF or KrF, or molecular fluorine (F₂) laser system for deep ultraviolet (DUV) or vacuum ultraviolet (VUV) lithography, is schematically shown. Alternative configurations for laser systems for use in such other industrial applications as TFT annealing and/or micromachining, e.g., are understood by one skilled in the art as being

The system shown in Fig. 1 generally includes a laser chamber 2 having a pair of main discharge electrodes 3 connected with a solid-state pulser module 4, and a gas handling module 6. The solid-state pulser module 4 is powered by a high voltage power supply 8. The laser chamber 2 is surrounded by optics module 10 and optics module 12, forming a resonator. The optics modules 10 and 12 are controlled by an optics control module 14, or may be alternatively directly controlled by a computer 16.

The computer 16 for laser control receives various inputs and controls various operating parameters of the system. A diagnostic module 18 receives and measures one or more parameters of a split off portion of the main beam 20 via optics for deflecting a small portion of the beam toward the module 18, such as preferably a beam splitter module 21, as shown. The beam 20 is preferably the laser output to an imaging system (not shown) and ultimately to a workpiece (also not shown), may be output directly to a application process. The laser

control computer 16 communicates through an interface 24 with a stepper/scanner computer 26 and other control units 28.

The laser chamber 2 contains a laser gas mixture and includes one or more preionization electrodes (not shown) in addition to the pair of main discharge electrodes 3. Preferred main electrodes 3 are described at U.S. patent applications no. 09/453,670, 60/184,705 and 60/128,227, each of which is assigned to the same assignee as the present application and is hereby incorporated by reference. Other electrode configurations are set forth at U.S. patents no. 5,729,565 and 4,860,300, each of which is assigned to the same assignee, and alternative embodiments are set forth at U.S. patents no. 4,691,322, 5,535,233 and 5,557,629, all of which are hereby incorporated by reference. Preferred preionization units are set forth at U.S. patent applications no. 60,162,845, 60/160,182, 60/127,237, 09/535,276 and 09/247,887, each of which is assigned to the same assignee as the present application, and alternative embodiments are set forth at U.S. patents no. 5,337,330, 5,818,865 and 5,991,324, all of the above patents and patent applications being hereby incorporated by reference.

The solid-state pulser module 14 and high voltage power supply 8 supply electrical energy in compressed electrical pulses to the preionization and main electrodes 3 within the laser chamber 2 to energize the gas mixture. The preferred pulser module and high voltage power supply are described at U.S. patent applications 60/149,392, 60/198,058, 60/204,095, 09/432,348 and 09/390,146, and U.S. patent application of Osmanow, et al., serial number not yet assigned, filed May 15, 2000, for "Electrical Excitation Circuit for Pulsed Laser", and U.S. patents no. 6,005,880 and 6,020,723, each of which is assigned to the same assignee as the present application and which is hereby incorporated by reference into the present application. Other alternative pulser modules are described at U.S. patents no. 5,982,800, 5,982,795, 5,940,421, 5,914,974, 5,949,806, 5,936,988, 6,028,872 and 5,729,562, each of which is hereby incorporated by reference. A

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conventional pulser module may generate electrical pulses in excess of 3 Joules of electrical power (see the '988 patent, mentioned above).

The laser resonator which surrounds the laser chamber 2 containing the laser gas mixture includes optics module 10 including line-narrowing optics for a line narrowed excimer or molecular fluorine laser, which may be replaced by a high reflectivity mirror or the like in a laser system wherein either line-narrowing is not desired, or if line narrowing is performed at the front optics module 12, or a spectral filter external to the resonator is used, or if the line-narrowing optics are disposed in front of the HR mirror, for narrowing the linewidth of the output beam. Several variations of line-narrowing optics in accord with the preferred embodiment are set forth in more detail below with reference to Figs. 2-7b.

The laser chamber 2 is sealed by windows transparent to the wavelengths of the emitted laser radiation 14. The windows may be Brewster windows or may be aligned at another angle to the optical path of the resonating beam. The beam path between the laser chamber and each of the optics modules 10 and 12 is sealed by enclosures 17 and 19, and the interiors of the enclosures is substantially free of water vapor, oxygen, hydrocarbons, fluorocarbons and the like which otherwise strongly absorb VUV laser radiation.

After a portion of the output beam 20 passes the outcoupler of the optics module 12, that output portion impinges upon beam splitter module 21 which includes optics for deflecting a portion of the beam to the diagnostic module 18, or otherwise allowing a small portion of the outcoupled beam to reach the diagnostic module 18, while a main beam portion 20 is allowed to continue as the output beam 20 of the laser system. Preferred optics include a beamsplitter or otherwise partially reflecting surface optic. The optics may also include a mirror or beam splitter as a second reflecting optic. More than one beam splitter and/or HR mirror(s), and/or dichroic mirror(s) may be used to direct portions of the beam to components of the diagnostic module 18. A holographic

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The output beam 20 may be transmitted at the beam splitter module while a reflected beam portion 22 is directed at the diagnostic module 18, or the main beam 20 may be reflected, while a small portion 22 is transmitted to the diagnostic module 18. The portion of the outcoupled beam which continues past the beam splitter module 21 is the output beam 20 of the laser, which propagates toward an industrial or experimental application such as an imaging system and workpiece for photolithographic applications. Variations of beam splitter modules particularly for a molecular fluorine laser system are set forth at U.S. patent application no. 60/140,530, which is assigned to the same assignee and is hereby incorporated by reference.

The diagnostic module 18 preferably includes at least one energy detector. This detector measures the total energy of the beam portion that corresponds directly to the energy of the output beam 20. An optical configuration such as an optical attenuator, e.g., a plate or a coating, or other optics may be formed on or near the detector or beam

splitter module 21 to control the intensity, spectral distribution and/or other parameters of the radiation impinging upon the detector (see U.S. patent applications no. 09/172,805, 60/172,749, 60/166,952 and 60/178,620, each of which is assigned to the same assignee as the present application and is hereby incorporated by reference).

One other component of the diagnostic module 18 is preferably a wavelength and/or bandwidth detection component such as a monitor etalon or grating spectrometer (see U.S. patent applications no. 09/416,344, 60/186,003, 60/158,808, and 60/186,096, and Lokai, et al., serial number not yet assigned, "Absolute Wavelength Calibration of Lithography Laser Using Multiple Element or Tandem See Through Hollow Cathode Lamp", filed May 10, 2000, each of which is assigned to the same assignee as the present application, and U.S. patents no. 4,905,243, 5,978,391, 5,450,207, 4,926,428, 5,748,346, 5,025,445, and 5,978,394, all of the above wavelength and/or bandwidth detection and monitoring components being hereby incorporated by reference.

Other components of the diagnostic module may include a pulse shape detector or ASE detector, such as are described at U.S. patent applications no. 09/484,818 and 09/418,052, respectively, each of which is assigned to the same assignee as the present application and is hereby incorporated by reference, such as for gas control and/or output beam energy stabilization. There may be a beam alignment monitor, e.g., such as is described at U.S. patent no. 6,014,206 which is hereby incorporated by reference.

The processor or control computer 16 receives and processes values of some of the pulse shape, energy, amplified spontaneous emission (ASE), energy stability, energy overshoot for burst mode operation, wavelength, spectral purity and/or bandwidth, among other input or output parameters of the laser system and output beam. The processor 16 also controls the line narrowing module to tune the wavelength and/or bandwidth or spectral purity, and controls the power supply and pulser module 4 and 8 to control preferably the moving

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average pulse power or energy, such that the energy dose at points on the workpiece is stabilized around a desired value. In addition, the computer 16 controls the gas handling module 6 which includes gas supply valves connected to various gas sources.

The laser gas mixture is initially filled into the laser chamber 2 during new fills. The gas composition for a very stable excimer laser in accord with the preferred embodiment uses helium or neon or a mixture of helium and neon as buffer gas, depending on the laser. Preferred gas compositions are described at U.S. patents no. 4,393,405 and 4,977,573 and U.S. patent applications no. 09/317,526, 09/513,025, 60/124,785, 09/418,052, 60/159,525 and 60/160,126, each of which is assigned to the same assignee and is hereby incorporated by reference into the present application. The concentration of the fluorine in the gas mixture may range from 0.003% to 1.00%, and is preferably around 0.1%. An additional gas additive, such as a rare gas, may be added for increased energy stability and/or as an attenuator as described in the 09/513,025 application incorporated by reference above. Specifically, for the F₂-laser, an addition of xenon and/or argon may be used. The concentration of xenon or argon in the mixture may range from 0.0001% to 0.1%. For an ArF-laser, an addition of xenon or krypton may be used also having a concentration between 0.0001% to 0.1%. For the KrF laser, an addition of xenon or argon may be used also having a concentration between 0.0001% to 0.1%.

Halogen and rare gas injections, total pressure adjustments and gas replacement procedures are performed using the gas handling module 6 preferably including a vacuum pump, a valve network and one or more gas compartments. The gas handling module 6 receives gas via gas lines connected to gas containers, tanks, canisters and/or bottles. Preferred gas handling and/or replenishment procedures of the preferred embodiment, other than as specifically described herein, are described at U.S. patents no. 4,977,573 and 5,396,514 and U.S. patent applications no. 60/124,785, 09/418,052, 09/379,034, 60/171,717, and

A general description of the line-narrowing features of the several embodiments of the present is first provided here, followed by a detailed discussion referring Figs. 2-7b. Exemplary line-narrowing optics contained in the optics module 10 include a beam expander, an optional etalon and a diffraction grating, which produces a relatively high degree of dispersion, for a narrow band laser such as is used with a refractive or catadioptric optical lithography imaging system. As mentioned above, the front optics module may include line-narrowing optics as well (see the 60/166,277, 60/173,993 and 60/166,967 applications, each being assigned to the same assignee and hereby incorporated by reference). For a semi-narrow band laser such as is used with an all-reflective imaging system, and which is not the subject of the present invention, the grating is replaced with a highly reflective mirror, and a lower degree of dispersion may be produced by a dispersive prism. A semi-narrow band laser would typically have an output beam linewidth in excess of 1 pm and may be as high as 100 pm in some laser systems, depending on the characteristic broadband bandwidth of the laser.

The beam expander of the above exemplary line-narrowing optics of the optics module 10 preferably includes one or more prisms. The beam expander may include other beam expanding optics such as a lens assembly or a converging/diverging lens pair. The grating or highly reflective mirror is preferably rotatable so that the wavelengths reflected into the acceptance angle of the resonator can be selected or tuned. Alternatively, the grating, or other optic or optics, or the entire line-narrowing module may be pressure tuned, such as is set forth in the 60/178,445 and 09/317,527 applications, each of which is assigned to the same assignee and is hereby incorporated by reference. The grating

may be used both for dispersing the beam for achieving narrow bandwidths and also preferably for retroreflecting the beam back toward the laser tube. Alternatively, a highly reflective mirror is positioned after the grating which receives a reflection from the grating and reflects the beam back toward the grating in a Littman configuration, or the grating may be a transmission grating. One or more dispersive prisms may also be used, and more than one etalon may be used.

Depending on the type and extent of line-narrowing and/or selection and tuning that is desired, and the particular laser that the line-narrowing optics are to be installed into, there are many alternative optical configurations that may be used. For this purpose, those shown in U.S. patents no. 4,399,540, 4,905,243, 5,226,050, 5,559,816, 5,659,419, 5,663,973, 5,761,236, and 5,946,337, and U.S. patent applications no. 09/317,695, 09/130,277, 09/244,554, 09/317,527, 09/073,070, 60/124,241, 60/140,532, 60/147,219 and 60/140,531, 60/147,219, 60/170,342, 60/172,749, 60/178,620, 60/173,993, 60/166,277, 60/166,967, 60/167,835, 60/170,919, 60/186,096, each of which is assigned to the same assignee as the present application, and U.S. patents no. 5,095,492, 5,684,822, 5,835,520, 5,852,627, 5,856,991, 5,898,725, 5,901,163, 5,917,849, 5,970,082, 5,404,366, 4,975,919, 5,142,543, 5,596,596, 5,802,094, 4,856,018, 5,970,082, 5,978,409, 5,999,318, 5,150,370 and 4,829,536, and German patent DE 298 22 090.3, are each hereby incorporated by reference into the present application.

Optics module 12 preferably includes means for outcoupling the beam 20, such as a partially reflective resonator reflector. The beam 20 may be otherwise outcoupled such as by an intra-resonator beam splitter or partially reflecting surface of another optical element, and the optics module 12 would in this case include a highly reflective mirror. The optics control module 14 preferably controls the optics modules 10 and 12 such as by receiving and interpreting signals from the processor 16,

Fig. 3b schematically shows a preferred grism 38 for use with the first embodiment of Fig. 3a having a dielectric HR coating on the grating surface 40. The grism 38 of Fig. 3b has the dielectric HR coating formed

Fig. 5a schematically shows a third embodiment of a laser resonator including a grism 58 for line-narrowing and/or selection. The grism has a transmissive grating surface 60 facing the discharge chamber 2. The grism 58 further includes a prism portion 61 having a highly reflective back surface 62 serving as a resonator reflector surface. The resonator shown also includes a prism beam expander 42 and a partially reflecting output coupler 44.

Fig. 6a schematically shows a fourth embodiment of a laser resonator including a grism 64 for line-narrowing and/or selection. The grism 64 has a transmissive grating surface 66 and a prism portion 67 having a transmissive beam entry/exit surface 68. A highly reflective mirror 70 is shown after the transmission grism to serve as a highly reflective resonator reflector. The resonator shown also includes a prism beam expander 42 before the grism 64 and a partially reflective outcoupler 44.

It is noted here that the number of prisms in the beam expanders 42 and/or 80 of Figs. 3a, 4a, 5a, 6a and 7a may be more or less than those shown. In addition, the grisms 51 and 64 of Figs. 4a and 6a, respectively, may be oriented such that their respective prism portions 52 and 67 do serve to refract the beam. In addition, the grism 64 of Fig. 6a may be turned around such that the prism portion 67 faces the discharge chamber 2. That prism portion 67 may be oriented to refract and expand

In all of the above embodiments shown and described with reference to Figs. 1-7, the material used for the prisms of the beam expanders, transmissive gratings or grisms, and laser windows is preferably one that is highly transparent at wavelengths of interest, such as 248 nm for the KrF laser, 193 nm for the ArF laser and 157 nm for the molecular fluorine laser. One or more etalons may be included in these resonator arrangements for further line-narrowing and/or selection made of a similar such material. The materials are also capable of withstanding long-term exposure to ultraviolet light with minimal degradation effects. Examples of such materials are CaF_2 , MgF_2 , BaF , BaF_2 , LiF , LiF_2 , SrF_2 , quartz and fluoro-doped quartz. Also, in all of the above embodiments of Figs. 1-7, many optical surfaces, particularly those of the prisms or etalons, preferably have an anti-reflective coating on one or more optical surfaces, in order to minimize reflection losses and prolong their lifetimes.

While exemplary drawings and specific embodiments of the present invention have been described and illustrated, it is to be understood that that the scope of the present invention is not to be limited to the particular embodiments discussed. Thus, the embodiments shall be regarded as illustrative rather than restrictive, and it should be understood that variations may be made in those embodiments by workers skilled in the arts without departing from the scope of the present invention as set forth in the claims that follow, and equivalents thereof.

For example, although the several embodiment described above include a grating or a grism disposed in the laser resonator on the opposite side of the discharge chamber 2 as the output coupler, a grism or grating may be disposed on the same side of the discharge chamber as the output coupler. In fact, the grating or grism may serve as the outcoupling element of the system, wherein the grating surface or back surface of the prism portion may be the partially reflective resonator

reflector surface, and the bulk of the grating or grism may be disposed inside or outside of the resonator. In addition, the resonator may include two highly reflecting resonator reflectors, and output coupling may be performed by reflection from an angled surface within the resonator, e.g., as described at U.S. patent no. 5,370,150, which is hereby incorporated by reference into the present application, wherein the grating or grism may be disposed on either side of the discharge chamber. In addition, more than one grating and/or grism may be included in the laser resonator.

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What is claimed is:

1. A grating element for use with a line-narrowing and/or line-selection package of an excimer or molecular fluorine laser having a dielectric highly reflective (HR) coating formed thereon.
2. An excimer or molecular fluorine laser system, including a line-narrowing and/or line-selection package for reducing the bandwidth of the laser beam to less than 1 pm, including a grating element having a dielectric HR coating formed thereon, the grating element for dispersing the beam and for retroreflecting the beam as a resonator reflector element.
3. A grating element for use with a line-narrowing and/or line-selection package of an excimer or molecular fluorine laser having a dielectric anti-reflective (AR) coating formed thereon.
4. An excimer or molecular fluorine laser system, including a line-narrowing and/or line-selection package for reducing the bandwidth of the laser beam to less than 1 pm, including a grating element for dispersing the beam having a dielectric AR coating formed thereon.
5. The laser system of Claim 4, wherein the grating element is disposed in front of a resonator reflector element.
6. The laser system of Claim 5, wherein the resonator reflector element is highly reflective.
7. The laser system of Claim 5, wherein the resonator reflector element is partially reflective as an output coupler.
8. A grism element for use with a line-narrowing and/or line-selection package of an excimer or molecular fluorine laser for dispersing

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the beam, said grism element having a grating surface and a prism portion.

9. The grism element of Claim 8, having a dielectric AR coating formed thereon.

10. The grism element of Claim 9, wherein the dielectric AR coating is formed on the grating surface.

11. The grism element of Claim 10, wherein a dielectric HR coating is formed on a rear surface of the prism portion.

12. The grism element of Claim 9, wherein a dielectric AR coating is formed on a rear surface of the prism portion.

13. The grism element of Claim 12, wherein a dielectric HR coating is formed on the grating surface.

14. The grism element of Claim 12, wherein a dielectric AR coating is formed on the grating surface.

15. The grism element of Claim 8, having a dielectric HR coating formed thereon.

16. The grism element of Claim 15, wherein the dielectric HR coating is formed on the grating surface.

17. The grism element of Claim 15, wherein the dielectric HR coating is formed on a rear surface of the prism portion.

18. An excimer or molecular fluorine laser system, including a discharge chamber disposed within a laser resonator having a line-

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narrowing and/or line selection package for reducing the bandwidth of the laser beam to less than 1 pm, including a grism element with a prism portion and a grating surface for dispersing the beam.

19. The laser system of Claim 18, wherein the grism element has a highly reflecting surface for reflecting the beam as a highly reflective resonator reflector.

20. The laser system of Claim 19, wherein the grating surface is the highly reflecting surface, and the grating surface faces the laser discharge chamber.

21. The laser system of Claim 19, wherein the grating surface is the highly reflecting surface, and the prism portion faces the laser discharge chamber.

22. The laser system of Claim 19, wherein a rear surface of the prism portion is the highly reflecting surface, and the grating surface faces the laser discharge chamber.

23. The laser system of Claim 18, wherein the grism element is disposed in the laser resonator in front of a highly reflective resonator reflector.

24. The laser system of Claim 23, wherein the grating surface has a dielectric AR coating formed thereon.

25. The laser resonator of any of Claims 19, 21 or 23-24, wherein a beam entry/exit surface of the prism portion has a dielectric AR coating formed thereon.

26. The laser resonator of Claim 25, wherein the grating surface has a dielectric HR coating formed thereon.

27 26. The laser resonator of any of Claims 19-21, wherein the grating surface has a dielectric HR coating formed thereon.

28 27. The laser system of any of Claims 18-19, 21 or 23, wherein the grism element is oriented such that the prism portion serves as a beam expander.

29 28. The laser system of Claim 18, wherein the grism element is disposed in the laser resonator in front of a partially reflective resonator output coupler.

30 29. The laser system of Claim 28, wherein the grating surface has a dielectric AR coating formed thereon.

31 30. The laser system of any of Claims 28-29, wherein a beam entry/exit surface of the prism portion has a dielectric AR coating formed thereon.

32 31. The laser system of Claim 18, wherein the grism is disposed within the laser resonator to serve as an output coupling element.

33 32. The laser system of Claim 31, wherein the grating surface faces the laser discharge chamber and has a dielectric AR coating formed thereon.

34 33. The laser system of Claim 31, wherein an entry exit surface of the grism faces the discharge chamber and has a dielectric AR coating formed thereon.

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35 34. The laser system of Claim 31, wherein the grating surface faces the laser discharge chamber and is partially reflective such that the grating surface serves as a resonator reflector surface.

36 35. The laser system of Claim 31, wherein a rear surface of the prism portion faces the discharge chamber and is partially reflecting such that the rear surface of the prism portion serves as a resonator reflector surface.

37 36. The laser system of any of Claims 18-24, further comprising a beam expander between the discharge chamber and the grism element.

38 37. The laser system of Claim 36, wherein the beam expander includes a plurality of DUV and/or VUV transparent prisms.

39 38. The laser system of Claim 37, wherein said plurality of prisms each has at least one dielectric AR coating formed thereon.

40 39. The laser system of Claim 36, further comprising an aperture disposed between the discharge chamber and the beam expander.

41 40. The laser system of Claim 36, further comprising an etalon within the resonator for further line-narrowing and/or line-selection.

42 41. The grating element of any of Claims 1 or 3, further comprising a bulk substrate having a plurality of grooves formed directly therein, wherein the dielectric coating is formed directly over said substrate and plurality of grooves.

43 42. The grating element of any of Claims 1 or 3, further comprising a bulk substrate having a ruled epoxy layer formed thereon

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43. The laser system of any of Claims 2 or 4, wherein the grating element further comprises a bulk substrate having a plurality of grooves formed directly therein, wherein the dielectric coating is formed directly over said substrate and plurality of grooves.

45. An excimer or molecular fluorine laser system, including a discharge chamber disposed within a laser resonator having a line-narrowing and/or line-selection package for reducing the bandwidth of the laser beam, including a grism element formed from a DUV and/or VUV transparent material, said grism having a prism portion and a grating surface, wherein the surface closest to the discharge chamber has an AR coating formed thereon.

47. The laser system of Claim 46, wherein a rear surface of said prism portion has a HR coating formed thereon.

48. The laser system of Claim 46, wherein a beam entry/exit surface of said prism portion has an AR coating formed thereon, wherein said laser system further comprises a highly reflective resonator reflector after said grism.

51 50. The laser system of Claim 45, wherein said surface closest to said discharge chamber is a beam entry/exit surface of said prism portion.

52. The laser system of Claim 50, wherein said grating surface has an AR coating formed thereon, wherein said laser system further comprises a highly reflective resonator reflector after said grism.

54. An excimer or molecular fluorine laser system, including a discharge chamber disposed within a laser resonator having a line-narrowing and/or line-selection package for reducing the bandwidth of the laser beam, including a grism element formed from a DUV and/or VUV transparent material, said grism having a prism portion and a grating surface, wherein the surface closest to the discharge chamber is partially reflecting and serves as a beam output coupler of said laser system.

57 56. The laser system of Claim 54, wherein said partially reflecting surface is a rear surface of said prism portion and said outcoupled beam exits said grism through said grating surface.

Abstract

A grating or grism element for use with a line-narrowing package of an excimer or molecular fluorine laser includes a highly reflective (HR) and/or an anti-reflective (AR) dielectric coating. The grating may also serve as a resonator reflector, thus having a dielectric HR coating. The grating may be disposed in front of an HR mirror and thus have a dielectric AR coating. The grating may be used as an output coupler and thus be partially reflective with or without a coating. The grism has a dielectric AR coating on any transmissive surface and a dielectric HR coating on any reflective surface. The grism may be configured to be disposed in the laser resonator with the grating surface facing the discharge chamber and serving as a HR reflecting resonator reflector. The prism portion may face the discharge chamber and the grating portion serving as a HR reflecting resonator reflector. The grating surface may face the discharge chamber and the rear surface of the prism portion may serve as a HR reflecting resonator reflector. The grism may be disposed in front of a HR resonator reflecting mirror or partially reflecting outcoupling mirror. The grism may serve as an output coupling element with either the grating surface or prism portion facing the discharge chamber, and, in either case, either the grating surface or prism portion serving as a partially reflecting resonator reflector surface. In this case, the surface that serves as the partially reflecting resonator reflector surface is partially reflecting and may be uncoated or coated, while the other surface has a dielectric AR coating on it. The grism may be disposed at a selected orientation with respect to the longitudinal cross-section of the resonator, such that the prism portion of the grism may serve as a beam expanding prism.

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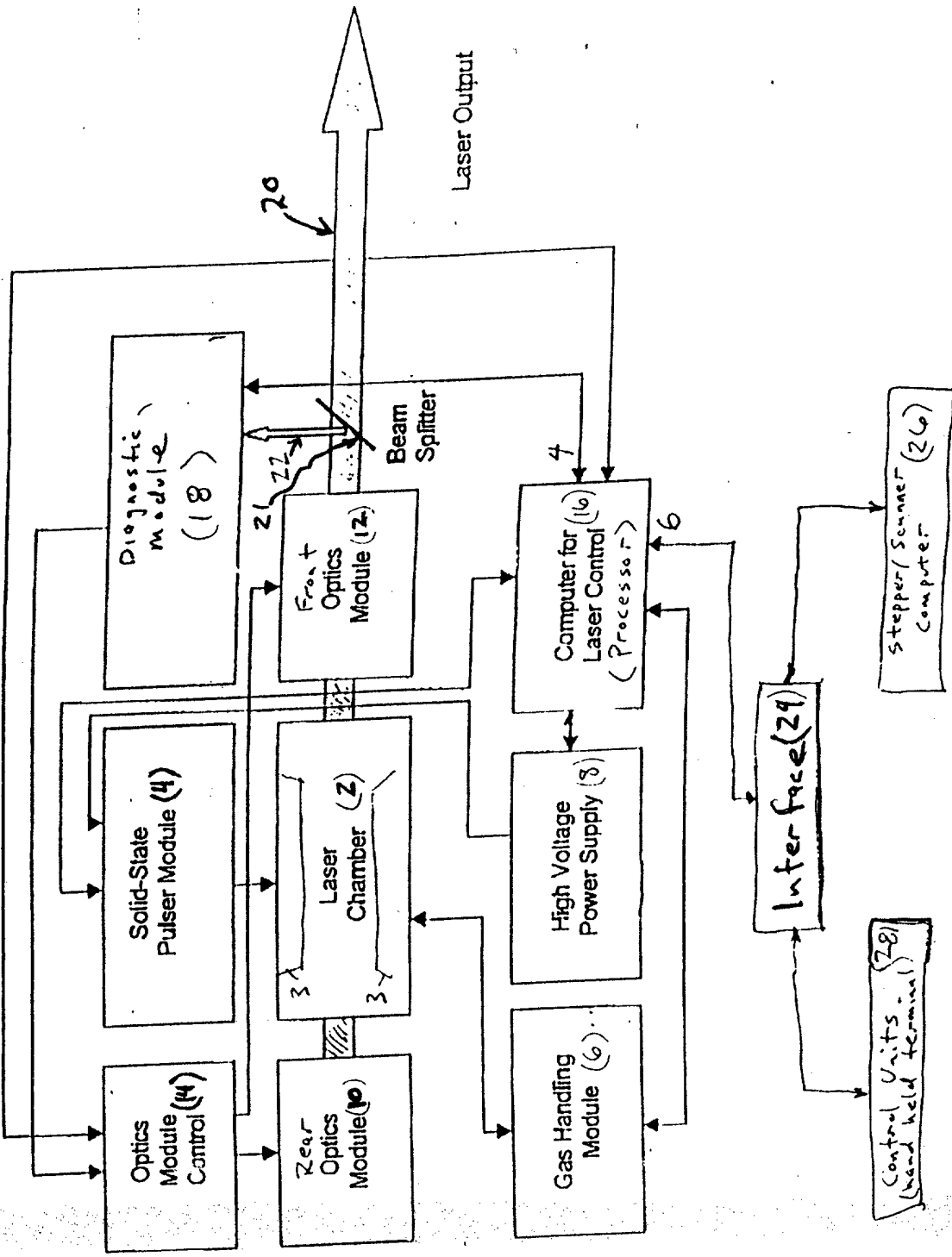


Fig. 1

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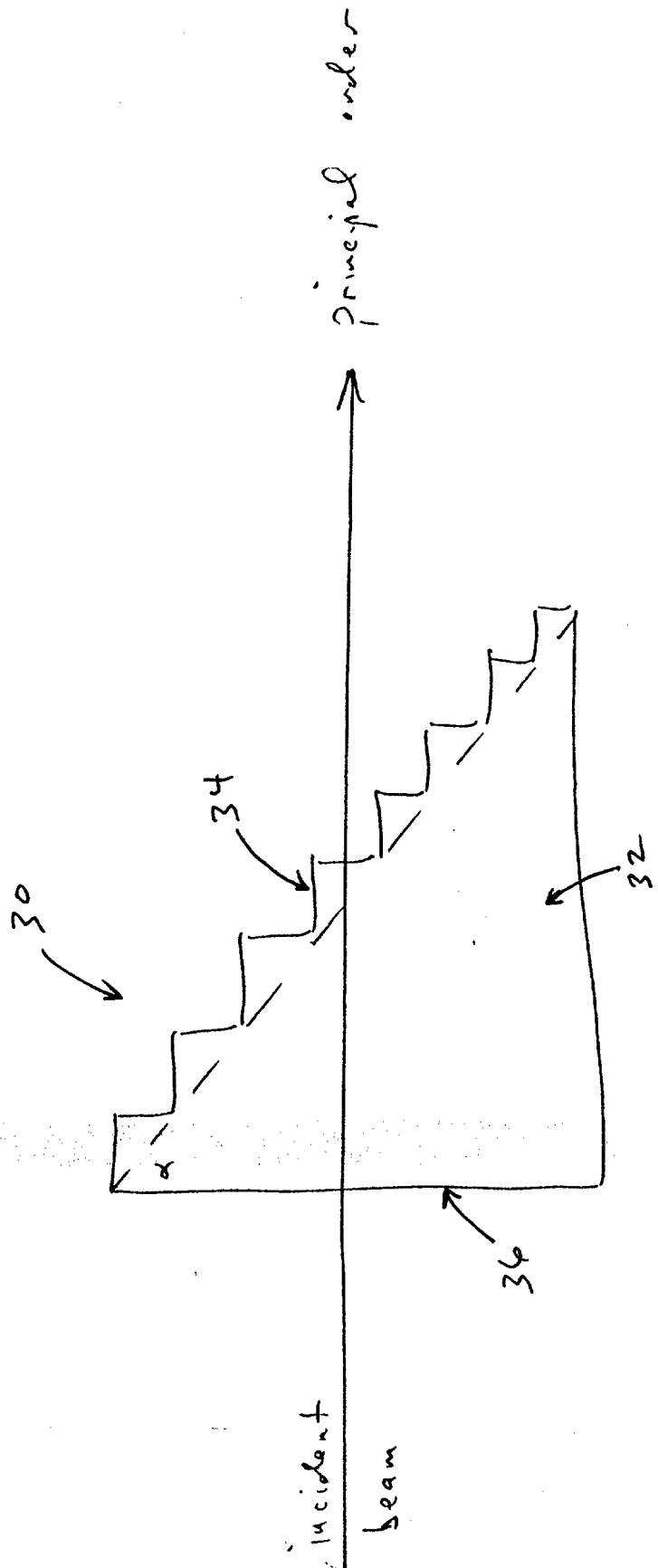


Fig. 2

DECLARATION FOR PATENT APPLICATION

As a below named inventor, I hereby declare that:

My residence, post office address and citizenship are as stated below next to my name,

I believe I am the original, first and sole inventor (if only one name is listed below) or an original, first and joint inventor (if plural names are listed below) of the subject matter which is claimed and for which a patent is sought on the invention entitled

NARROW BAND EXCIMER LASER WITH A PRISM-GRATING AS LINE-NARROWING OPTICAL ELEMENT

the specification of which (check one) X is attached hereto or ___ was filed on ___ as Application No. ___ and was amended on ___ (if applicable).

I hereby state that I have reviewed and understand the contents of the above-identified specification, including the claims, as amended by any amendment referred to above.

I acknowledge the duty to disclose all information which is material to patentability as defined in 37 CFR § 1.56.

I hereby claim foreign priority benefits under 35 U.S.C. § 119(a)-(d) or § 365(b) of any foreign application(s) for patent or inventor's certificate, or § 365(a) of any PCT International application which designated at least one country other than the United States, listed below and have also identified below any foreign application for patent or inventor's certificate having a filing date before that of the application on which priority is claimed:

Prior Foreign Application(s)	Priority Claimed	
	Yes	No
Number		
Country		
Day/Month/Year Filed		

I hereby claim the benefit under 35 U.S.C. § 119(e) of any United States provisional application(s) below.

<u>60/140,532</u>	<u>June 23, 1999</u>
Application Number	Filing Date
<u>60/173,993</u>	<u>December 30, 1999</u>
Application Number	Filing Date
<u>60/170,919</u>	<u>December 15, 1999</u>
Application Number	Filing Date
<u>60/167,835</u>	<u>November 29, 1999</u>
Application Number	Filing Date

I hereby claim the benefit under 35 U.S.C. § 120 of any United States application(s), or § 365(c) of any PCT International application designating the United States, listed below and, insofar as the subject matter of each of the claims of this application is not disclosed in the prior United States application in the manner provided by the first paragraph of 35 U.S.C. § 112, I acknowledge the duty to disclose all information which is material to patentability as defined in 37 CFR § 1.56 which became available between the filing date of the prior application and the national or PCT international filing date of this application:

[illegible]

Inventor's signature _____ Date _____

Citizenship Germany

Full name of second joint inventor, if any, Thomas Schroeder

Inventor's signature _____ Date _____

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